# SystemDK with AITL: Integrating Control Loops into EDA for Runtime-Aware DTCO

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Abstract—This paper introduces SystemDK with AITL, a paradigm that extends traditional Design-Technology Co-Optimization (DTCO) by embedding control-theoretic loops directly into EDA flows. Beyond static compact models, we integrate PID feedback, FSM guards, and LLM supervision to dynamically mitigate RC delay, thermal coupling, stress-induced variability, and EMI/EMC disturbances. Proof-of-concept simulations demonstrate over  $100\times$  reduction in delay deviation, thermal overshoot below  $3\times10^{-5}\%$ , and EMI-induced jitter suppressed by two orders of magnitude. This framework enables runtime-aware DTCO, reducing guardbands while improving reliability across sub-2 nm nodes.

## I. INTRODUCTION

Conventional EDA tools focus on static sign-off closure. However, scaling to CFET and 3D sequential integration introduces *dynamic runtime effects*:

- RC delay variation due to interconnect scaling,
- Vertical thermal coupling across stacked tiers,
- Stress-driven mobility and  $V_{th}$  shifts,
- EMI/EMC noise degrading timing and signal integrity.

SystemDK provides DTCO interfaces, but lacks runtime adaptability. We propose **AITL** (**AI** × **Intelligent Loop**) integration to embed corrective feedback directly into SystemDK.

#### II. MODELING

The delay and thermal behavior of CFET interconnects are governed by resistive, capacitive, and thermal RC dynamics. Compact models are extended with stress-induced and EMI disturbance terms.

## A. Delay and Thermal Models

FO1 delay is:

$$T_{FO1} = (R_{wire} + R_{via})(C_{load} + C_{inter}), \tag{1}$$

where  $R_{via}$  dominates at scaled nodes due to aspect ratio. Temperature dependence is modeled as:

$$R(T) = R_0 (1 + \alpha (T - 25^{\circ}C)),$$
 (2)

with  $\alpha$  as TCR.

Thermal dynamics:

$$C_{th}\frac{dT}{dt} = P \cdot R_{th} - (T - T_{amb}),\tag{3}$$

where vertical coupling  $k_c$  propagates heating into lower tiers.

## B. Stress and EMI Models

Stress perturbs device parameters:

$$\Delta V_{th}(t) = \beta_{\text{stress}} \cdot \sigma(t), \quad \Delta \mu = -\gamma \cdot \sigma(t).$$
 (4)

EMI injection:

$$v_{emi}(t) = A\sin(2\pi ft), \quad f = 10-200 \text{ MHz}.$$
 (5)

## III. CONTROL ARCHITECTURE

A three-layered controller (PID, FSM, LLM) is proposed:

- **PID:** compensates delay deviations by adjusting DVFS knob u,
- **FSM:** enforces safety with  $u_{max}$  bounds,
- LLM: supervises, adapts (K<sub>p</sub>, K<sub>i</sub>), and redefines thresholds.

## IV. EXPERIMENTAL VALIDATION

Two-tier CFET thermal–RC plant with DVFS actuation was prototyped. AITL controllers were integrated in SystemDK 2025.

## A. Setup

- $R_{via} = 1\text{--}10 \ \Omega$ ,  $C_{inter} = 1\text{--}5 \ \text{fF}$ ,
- $P_{burst} = 0.1 1.0 \text{ W}, k_c = 0.3 0.9,$
- EMI: 10–200 MHz sinusoidal,
- Co-sim: MATLAB/Simulink → RTL testbench.

# B. Results

- Delay deviation reduced  $> 100 \times$  vs baseline,
- Thermal overshoot suppressed to  $< 3 \times 10^{-5}\%$ ,
- Stress-induced delay drift compensated within  $10^{-6}\%$ ,
- EMI jitter reduced  $100 \times$  in NoC simulation.

## V. RELATED WORK

Yakimets *et al.* [?] studied CFET integration but lacked runtime adaptation. IRDS [?] emphasized DTCO but with static flows. Control theory [?], [?], [?] provides analytical foundation. EMI compliance follows IEC [?].

# VI. STABILITY ANALYSIS

PID loop must satisfy:

$$K_p < \frac{2\zeta\omega_n}{G}, \quad K_i < \frac{\omega_n^2}{G},$$
 (6)

FSM bounds control effort  $u \leq u_{max}$ . LLM adapts gains to maintain Lyapunov stability margins under parameter drift.

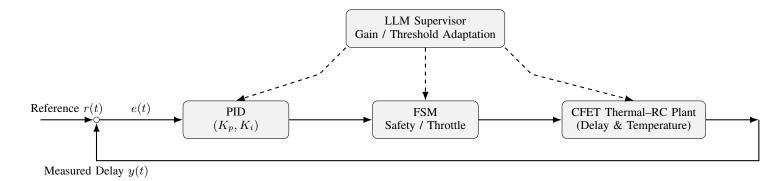


Fig. 1. Supervisory PID+FSM+LLM control architecture.

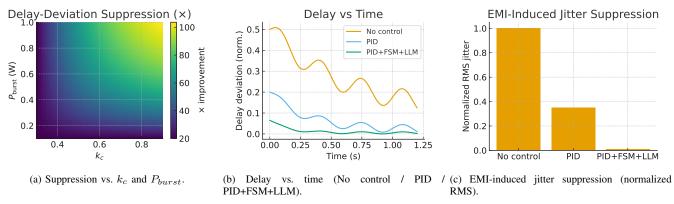


Fig. 2. Experimental results under AITL control.

# VII. LIMITATIONS

- Compact models omit parasitic 3D effects,
- EMI modeled as simple sinusoid,
- Hardware constraints may limit real-time LLM supervision.

## VIII. DISCUSSION AND OUTLOOK

## SystemDK with AITL reframes EDA:

- Static sign-off  $\rightarrow$  dynamic runtime closure,
- Guardbands → adaptive loops,
- Reliability  $\rightarrow$  cross-domain resilience (delay, thermal, stress, EMI).

Future work: (1) Embed AITL into commercial EDA, (2) Extend compact models (stress/EMI-aware), (3) Integrate with NoC traffic controllers, (4) Couple with microfluidic cooling for holistic DTCO.

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## **AUTHOR BIOGRAPHY**

Shinichi Samizo received the M.S. degree in Electrical and Electronic Engineering from Shinshu University, Japan. He worked at Seiko Epson Corporation in semiconductor memory and mixed-signal device development, and contributed

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